

Title (en)

MICROLITHOGRAPHIC PROJECTION ILLUMINATION SYSTEM, OPTICAL SYSTEM, METHOD FOR THE PRODUCTION OF A MICROLITHOGRAPHIC PROJECTION LENS SYSTEM AND MICROLITHOGRAPHIC STRUCTURING METHOD

Title (de)

PROJEKTIONSBELICHTUNGSANLAGE DER MIKROLITHOGRAPHIE

Title (fr)

DISPOSITIF D'INSOLATION PAR PROJECTION POUR MICROLITHOGRAPHIE, SYSTEME OPTIQUE, PROCEDE DE FABRICATION D'UN OBJECTIF DE PROJECTION POUR MICROLITHOGRAPHIE ET PROCEDE DE STRUCTURATION MICROLITHOGRAPHIQUE

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Application

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Abstract (en)

[origin: US2004150806A1] A projection exposure apparatus for microlithography has a light source, an illumination system, a mask-positioning system and a projection lens. The latter has a system aperture plane and an image plane and contains at least one lens that is made of a material which has a birefringence dependent on the transmission angle. The exposure apparatus further has an optical element, which has a position-dependent polarization-rotating effect or a position-dependent birefringence. This element, which is provided close to a pupil plane of the projection exposure apparatus, compensates at least partially for the birefringent effects produced in the image plane by the at least one lens.

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IPC 8 full level

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CPC (source: EP KR US)

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